

Ain Shams University
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Investigation of Some Physical Properties of SnS Thin Films Using Electrical and Optical Measurements

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قالوا سبحانك لا علم لنا إلا ما علمتنا
إنك أنت العزيز الحكيم

صدق الله العظيم

(سورة البقرة- آية - ٣٢)

إهداء

أُهِرَى هَذَا الْعَمَلُ الْمَتَوَاضِعُ
إِلَى كُلِّ أَهْلِي وَعَشِيرَتِي
الَّذِينَ تَحْنُونَا وَوَعَدُوا لِي بِالكَثِيرِ
وَتَحْمِلُونَا وَعَانُوا مَعِيَ الْكَثِيرَ

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Contents

	Page
List of Plates and figures	i
List of Tables	ii
ABSTRACT	iii
SUMMARY	iv
INTRODUCTION	1
CHAPTER I : LITERATURE REVIEW AND THEORITICAL BACKGROUND	2
I.1 Structural properties of Tin Sulphide Material	2
I.2 The Electronic Band Structure of SnS	11
I.3 Transport Properties of SnS	13
I.4 Optical Properties of SnS	24
CHAPTER II : EXPERIMENTAL TECHNIQUES	43
II.1 Material Under Investigation	43
II.2 Preparation of SnS Thin Films	43
II.2.a) Cleaning of the Glass and Quartz Substrates	43
II.2.b) Evaporation Technique	44
II.3 Methods for Film Thickness Measurements	46
II.3.a) Quartz Crystal Thickness Monitor Technique	46
II.3.b) Interferometric Technique	47
II.4 Structural Identification of the Investigated Samples	52
II.4.a) X-ray Diffraction	53
II.4.a.1) Correction and Normalization of the x-ray Intensities	53
i) Correction	53
ii) Normalization of the x-ray Intensities to Absolute Units	55
II.4.a.2) Minimization process, Evaluation of the Background Scattering and the Resolution of the overlapped peaks	55

II.4.a.3)	Crystallite Sizes and Lattice Distortion	56
II.4.a.4)	Determination of the Ideal crystallite Sizes	57
II.4.b)	Transmission Electron Microscopy	58
II.4.b.1)	Electron Diffraction	58
II.4.b.2)	Preparation of SnS Thin Films for Microscopic observation	60
II.5)	Transport Properties Measurements	64
II.5.a)	Electrical Resistivity Measurements	64
II.5.b)	Thermoelectric Power Measurements	65
II.5.c)	Current-Voltage Characteristics Measurements	71
II.6)	Determination of the Optical constants of SnS Thin Films	71
II.6.a)	The Transmittance $T(\lambda)$ at Normal Light Incidence	73
II.6.b)	The Reflectance $R(\lambda)$ at Normal incidence	76
II.6.c)	A computational Technique for Determining the Optical Constant $n(\lambda)$ and $k(\lambda)$ of thin Films	77
CHAPTER III: STRUCTURAL PROPERTIES OF SnS MATERIAL		84
III.1	X-ray Diffraction Analysis of SnS in Powder Form	84
III.2	The Structural Dependence on Film Thicknesses of SnS Thin Films	84
III.3	Structural Dependence on the Annealing Temperature for the SnS thin films	89
III.4	Crystallite Sizes and Lattice Strains of SnS Thin Films	89
III.5	Electron Diffraction Studies of SnS Thin Films	101
CHAPTER IV: OPTICAL PROPERTIES OF SnS THIN FILMS		105

IV.1	The Spectral Distribution of the Transmission $T(\lambda)$ and Reflection $R(\lambda)$ of SnS Thin Films	106
IV.2	The Spectral Distribution of both the Refractive Index $n(\lambda)$ and the Absorption Index $k(\lambda)$ of SnS Thin Films	106
IV.3	The Lattice Dielectric Constant ϵ_L of SnS Thin Films	109
IV.4	The Spectral Distribution of the Absorption Coefficient (α) of SnS Thin Films	113
IV.5	The Allowed Optical Transitions in SnS Thin Films ..	113
CHAPTER V: ELECTRICAL TRANSPORT PROPERTIES OF SnS THIN FILMS		
V.1	Dark Electrical Resistivity of SnS Thin Film	123
V.1.a)	Dark Electrical Resistivity Dependence of the SnS Film Thickness	123
V.1.b)	Dark Electrical Resistivity Dependence of the SnS Film Temperature	127
V.1.c)	Dark Electrical Resistivity Dependence of the Annealing Temperature	135
V.2.	Thermoelectric Power (Seebeck Coefficient S) of SnS Thin Films	135
V.2.a)	Seebeck Coefficient Dependence of the SnS Film Thickness	135
V.2.b)	Seebeck Coefficient Dependence of the Annealing Temperature	142
V.3.	The Current-Voltage Characteristics of p-SnS/n-Si Heterojunction	152
V.3.a)	Static I-V characteristics of a p-SnS/n-Si Heterojunction	152
V.3.a.i)	Determination of the Base Resistance R_b ...	155
V.3.a.ii)	Forward Current Activation Energy	157
V.3.a.iii)	Reverse Current Activation Energy	159
V.3.a.iv)	Rectification Ratio	162

V.3 a.v) The Conduction Mechanism	162
V.3.b) Capacitance-Voltage (C-V) Characteristics of p-SnS/n-Si Heterojunction	170
CONCLUSIONS	171
REFERENCES	175
ARABIC SUMMARY	

List of Plates and Figures

	Page
Plate (1) : A photograph of the coating unit (type E 306 A Edwards, England).....	45
Plate (2) : A photograph of the Thickness Monitor (Model FTM4, Edwards, England).....	48
Plate (3) : The x-ray Diffractometer (type PW 1373, Philips).	54
Plate (4) : Electron Diffraction pattern of thin polycrystalline vacuum deposited gold film At 60 kV.....	62
Plate (5) : A photograph of the Double Beam Spectrophotometer (CARY 2390, Varian Co.).	74
Plate (6) : The electron diffraction pattern of SnS thin film (30 nm thick) deposited onto glass substrate...	102
Plate (7) : The electron diffraction pattern of SnS thin film (60nm thick) deposited onto glass substrate.	102
Fig.(1) : Crystal structure of SnS according to Hofmann...	3
Fig.(2) : Transformation of SnS from orthorhombic crystal to cubic.....	5
Fig. (3) : The Brillouin Zone appropriate to SnS.....	12
Fig. (4) : A plane monochromatic light at normal incident on an absorbing film between the two dielectric media air and quartz.....	41
Fig. (5) : Schematic diagram of the interferometer used for thickness measurement.....	50
Fig. (6) : The optical set-up for producing multiple beam Fizeau fringes at reflection.....	50
Fig. (7) : The Multiple-beam Fizeau fringes with step..	51
Fig. (8) : Relation between the ring radii and $(h^2+k^2+l^2)^{1/2}$ of allowed reflecting planes of f.c.c.gold.....	63
Fig. (9) : A Schematic diagram of the film electrode system.	66

Fig. (10):	Cryostat used for resistivity measurements.	67
Fig. (11):	Holder used for thermoelectric power measurements.	70
Fig. (12):	Electric circuit for current-voltage characteristics of p-n heterojunction.....	72
Fig. (13):	Simplified optical, schematic (A) in the V case and (B) in the W case.	75
Fig. (14):	Flow chart diagram of program used for n and k calculation.....	79
Fig. (15):	Plot of n versus variance for different values of k, $t/\lambda = 0.1$, $T_{exp} = 0.484$ and $R_{exp} = 0.327$	80
Fig. (16):	Flow chart diagram of step-length optimisation technique.....	82
Fig. (17):	X-ray diffraction pattern of original SnS powder.	85
Fig. (18):	X-ray diffraction patterns of SnS thin films with different thickness.....	88
Fig. (19):	X-ray diffraction patterns of SnS thin films (400 nm thick) deposited at room temperature then annealed at the temperatures marked on the curves.....	90
Fig. (20):	The profiles of SnS powder annealed at 300°C for five hours.....	93
Fig. (21):	The profiles of the resolved (111,130) reflection planes of SnS thin film (400 nm thick) as deposited.	94
Fig. (22):	The profiles of the resolved (111,130) reflection planes of SnS thin film (400 nm thick) annealed at 60°C.....	95
Fig. (23):	The profiles of the resolved (111,130) reflection planes of SnS thin film (400nm thick) annealed at 100°C.....	96
Fig. (24):	The profiles of the resolved (111,130) reflection planes of SnS thin film (400nm thick) annealed at 150°C.....	97

Fig. (25): The profiles of the resolved (111,130) reflection planes of SnS thin film (400 nm thick) annealed at 200°C.....	98
Fig. (26): The spectral distribution of the transmission $T(\lambda)$ for SnS thin films with different thicknesses.....	107
Fig. (27): The spectral distribution of reflection $R(\lambda)$ for SnS thin films with different thicknesses.....	108
Fig. (28): Dispersion curves of both n and k for the as-deposited SnS thin films.....	110
Fig. (29): The real dielectric constant ϵ_r as a function of λ^2 for SnS thin films.....	112
Fig. (30): The absorption coefficient (α) of SnS thin films as a function of the photon energy ($h\nu$).....	115
Fig. (31): Dependence of $(\alpha h\nu)^{1/2}$ on the photon energy ($h\nu$) for SnS thin films.....	119
Fig. (32): Dependence of $(\alpha h\nu)^2$ on the photon energy ($h\nu$) for SnS thin films.....	120
Fig. (33): The relation between $\log((\alpha h\nu))$ and $\log(\frac{1}{\lambda})$ for SnS thin films.....	121
Fig. (34): I-V relation for SnS thin film with Al electrodes.	124
Fig. (35): I-V relation for SnS thin film with Ag electrodes.	125
Fig. (36): The dark electrical resistivity (P) of SnS films versus the film thickness (t).....	126
Fig. (37): Temperature dependence of the electrical resistivity of SnS thin film of thickness (60nm).	128
Fig. (38): Temperature dependence of the electrical resistivity of SnS thin film of thickness (100nm).	129
Fig. (39): Temperature dependence of the electrical resistivity of SnS thin film of thickness (130nm).....	130
Fig. (40): Temperature dependence of the electrical resistivity of SnS thin film of thickness (140nm).....	131

Fig. (41):	Temperature dependence of the electrical resistivity of SnS thin films of thickness (180nm).....	132
Fig. (42):	Temperature dependence of the electrical resistivity of SnS thin film of thickness (230nm).....	133
Fig. (43):	Temperature dependence of the electrical resistivity of SnS thin film (120nm thick) as deposited.....	136
Fig. (44):	Temperature dependence of the electrical resistivity of SnS thin film (120nm thick) annealed at 100°C for two hours.....	137
Fig. (45):	Temperature dependence of the electrical resistivity of SnS thin film (120nm thick) annealed at 125°C for two hours.....	138
Fig. (46):	Temperature dependence of the electrical resistivity of SnS thin film (120nm thick) annealed at 150°C for two hours.....	139
Fig. (47):	Temperature dependence of the electrical resistivity of SnS thin film (120nm thick) annealed at 175°C for two hours.....	140
Fig. (48):	Seebeck coefficient (S) versus temperature (T) for SnS thin film (160nm thick) as deposited.....	143
Fig. (49):	Seebeck coefficient (S) versus temperature (T) for SnS thin film (300nm thick) as deposited.....	144
Fig. (50):	Seebeck coefficient (S) versus temperature (T) for SnS thin film (330nm thick) as deposited.....	145
Fig. (51):	Seebeck coefficient (S) versus temperature (T) for SnS thin film (417.6nm thick) as deposited...	146
Fig. (52):	Seebeck coefficient (S) versus temperature (T) for SnS thin film (160nm thick) annealed at 100°C for two hours.....	147
Fig. (53):	Seebeck coefficient (S) versus temperature (T) for SnS thin film (417.6nm thick) annealed at 100°C for two hours.....	148

Fig. (54): Seebeck coefficient (S) versus temperature (T) for SnS thin film (160nm thick) annealed at 170°C for two hours.....	149
Fig. (55): Seebeck coefficient (S) versus temperature (T) for SnS thin film (417.6nm thick) annealed at 170°C for two hours.....	150
Fig. (56): I-V characteristics for pre-annealed P-SnS/n-Si heterojunction at different ambient temperatures..	154
Fig. (57): Ln (Base resistance R_b) versus $\frac{1000}{T} K^{-1}$	156
Fig. (58): Ln (forward current I_f) versus $\frac{1000}{T} K^{-1}$	158
Fig. (59): Forward current activation energy ΔE_f as a function of the applied forward voltage V_f	158
Fig. (60): Ln (reverse current I_r) versus $\frac{1000}{T} K^{-1}$	160
Fig. (61): Reverse current activation energy ΔE_r as a function of the applied reverse voltage.....	161
Fig. (62): The rectification ratio (RR) versus voltage.....	163
Fig. (63-67): LogI versus the applied voltage at a given temperature.....	164-168
Fig. (68): Log I_0 versus T k.....	169